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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/688,974	10/21/2003	Howard E. Rhodes	M4065.0650/P650	8113	
24998	7590 04/21/2005		EXAMINER		
	N SHAPIRO MORIN & (WILSON,	WILSON, SCOTT R		
	2101 L Street, NW Washington, DC 20037			PAPER NUMBER	
_			2826		
				DATE MAILED: 04/21/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/688,974	RHODES, HOWARD E.			
Office Action Summary	Examiner	Art Unit			
_	Scott R. Wilson	2826			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period was railure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tim within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from to cause the application to become ABANDONED	ely filed will be considered timely. the mailing date of this communication. 0 (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on 03 February 2005.					
2a) ☐ This action is FINAL . 2b) ☐ This	☐ This action is FINAL. 2b)☐ This action is non-final.				
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4) ⊠ Claim(s) 11-44 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) ⊠ Claim(s) 39 and 44 is/are allowed. 6) ⊠ Claim(s) 11-13,26,34-38 and 40-43 is/are rejected. 7) ⊠ Claim(s) 14-25 and 27-33 is/are objected to. 8) □ Claim(s) are subject to restriction and/or election requirement.					
Application Papers					
9)☐ The specification is objected to by the Examine	ſ.				
10)⊠ The drawing(s) filed on <u>21 October 2003</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.					
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priori application from the International Bureau * See the attached detailed Office action for a list of	s have been received. s have been received in Application ity documents have been receive (PCT Rule 17.2(a)).	on No d in this National Stage			
Attachment(s)					
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary (Paper No(s)/Mail Da 5) Notice of Informal Pa 6) Other:				

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 11-13 are rejected under 35 U.S.C. 102(b) as being anticipated by Corrie et al.. As to claim 11, Corrie et al., Figure 4, discloses more than two non-overlapping gate structures (42), (32), (22) and (43) (col. 4, lines 55-56, 43-44 and 10) formed in a single layer on said substrate, said gate structures spaced apart by a gap of from 700 to 1000 Angstroms (col. 4, line 35).

As to claim 12, Corrie et al. discloses (col. 4, line 35) that the gap is greater than 300 Angstroms.

As to claim 13, Corrie et al., discloses (col. 4, lines 55-56, 43-44 and 10) that the gate structures are formed from polysilicon.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claim 26 is rejected under 35 U.S.C. 103(a) as being unpatentable over Corrie et al. in view of Ackland et al.. Corrie et al., Figure 4, discloses more than two non-overlapping gate structures (42), (32), (22) and (43) (col. 4, lines 55-56, 43-44 and 10) formed in a single layer on said substrate, said gate structures spaced apart by a gap of from 700 to 1000 Angstroms (col. 4, line 35). Corrie et al. does not disclose expressly a lightly doped region in the substrate between two adjacent ones of the plurality of

conductive gates. Ackland et al., Figure 3, discloses a semiconductor device comprising a substrate, a plurality of conductive gates (101) and (108) formed over the substrate, and a lightly doped region (112) in the substrate between the two adjacent conductive gates (101) and (108). At the time of invention, it would have been obvious to a person of ordinary skill in the art to form the lightly doped regions of Ackland et al. under the gate structures of Corrie et al.. The motivation for doing so would have been to allow the lightly doped region (112) to act as a source (Ackland et al., col. 5, lines 5-10). Therefore, it would have been obvious to combine Ackland et al. with Corrie et al. to obtain the invention as specified in claim 26.

Claims 34-38 are rejected under 35 U.S.C. 103(a) as being unpatentable over Corrie et al. in view of Ackland et al.. As to claim 34, Corrie et al., Figure 4, discloses more than two non-overlapping gate structures (42), (32), (22) and (43) (col. 4, lines 55-56, 43-44 and 10) formed in a single layer on said substrate, said gate structures spaced apart by a gap of from 700 to 1000 Angstroms (col. 4, line 35). Corrie et al. does not disclose expressly an image sensor or image processor. Ackland et al., Figures 1 and 2, discloses an image processing apparatus comprising an image sensor (101) for detecting an image and outputting image signals corresponding to the detected image, and an image processor (120), (125), (130) and (135) for processing the image signals outputted from the image sensor, wherein the image sensor comprises a substrate and two gate structures formed in a single layer on said substrate, said gate structures being spaced apart by a gap of a few tens of nanometers (col. 3, lines 60-63), which may be in the range of from 10 nm to 90 nm. At the time of invention, it would have been obvious to a person of ordinary skill in the art to form the image sensor and image processor of Ackland et al. with the gate structures of Corrie et al.. The motivation for doing so would have been to enable imaging of objects. Therefore, it would have been obvious to combine Ackland et al. with Corrie et al. to obtain the invention as specified in claim 34.

As to claim 35, Ackland et al., Figure 2 (col. 3, lines 60-63), discloses that the gap is within the scope of being from 30 nm and 100 nm.

As to claim 36, Ackland et al. discloses (col. 2, lines 43-47) that the gate structure shown in Figure 2 is in a CMOS active pixel, which is within the scope of being an imager. Although Ackland et al.

does not expressly disclose that the gate structure is part of a CCD imager, it is understood in the art that CCD imagers and CMOS imagers operate under the same charge-transfer mechanism. See, for example, applicants Background of the Invention, or Fossum et al., col. 1, lines 35-43).

As to claim 37, Ackland et al. discloses (col. 2, lines 43-47) that the gate structure shown in Figure 2 is in a CMOS active pixel, which is within the scope of being an imager.

As to claim 38, Ackland et al., Figure 3, discloses an embodiment with a photo gate (101) and transfer gate (108) (col. 5, lines 16-17) with a lightly doped region (112) between the two adjacent gate structures.

Claims 40-43 are rejected under 35 U.S.C. 103(a) as being unpatentable over Corrie et al. in view of Ackland et al.. As to claim 40, Corrie et al., Figure 4, discloses more than two non-overlapping gate structures (42), (32), (22) and (43) (col. 4, lines 55-56, 43-44 and 10) formed in a single layer on said substrate, said gate structures spaced apart by a gap of from 700 to 1000 Angstroms (col. 4, line 35). Corrie et al. does not disclose expressly an image sensor or image processor. Ackland et al., Figures 1 and 2, discloses a processing system comprising a processor for receiving and processing image data (35), and an image data generator (101), (107) for supplying image data to the processor, the image data generator comprising an image sensor for obtaining an image and outputting an image signal (35), an image processor (120), (125), (130) and (135) for processing the image signal and a controller (190) for controlling the image sensor and the image processor, wherein the image sensor comprises a substrate and two gate structures formed in a single layer on said substrate, said gate structures being spaced apart by a gap of a few tens of nanometers (col. 3, lines 60-63), which may be in the range of from 10 nm to 90 nm. At the time of invention, it would have been obvious to a person of ordinary skill in the art to form the image sensor and image processor of Ackland et al. with the gate structures of Corrie et al.. The motivation for doing so would have been to enable imaging of objects. Therefore, it would have been obvious to combine Ackland et al. with Corrie et al. to obtain the invention as specified in claim 40.

As to claim 41, Ackland et al. discloses (col. 2, lines 43-47) that the gate structure shown in Figure 2 is in a CMOS active pixel, which is within the scope of being an imager. Although Ackland et al. does not expressly disclose that the gate structure is part of a CCD imager, it is understood in the art that

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CCD imagers and CMOS imagers operate under the same charge-transfer mechanism. See, for example, applicants Background of the Invention, or Fossum et al., col. 1, lines 35-43).

As to claim 42, Ackland et al. discloses (col. 2, lines 43-47) that the gate structure shown in Figure 2 is in a CMOS active pixel, which is within the scope of being an imager.

As to claim 43, Ackland et al., Figure 3, discloses an embodiment with a photo gate (101) and transfer gate (108) (col. 5, lines 16-17) with a lightly doped region (112) between the two adjacent gate structures.

Allowable Subject Matter

Claims 14-25 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims. No prior art discloses that claimed invention where the gate structures are transistor gates with or without lightly doped regions therebetween.

Claims 27 and 28 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims. No prior art discloses the claimed invention with a specific doping concentration for the lightly doped region.

Claims 29-33 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims. No prior art discloses that claimed invention where the gate structures are transistor gates with or without lightly doped regions therebetween.

Claims 39 and 44 are allowed.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office

action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of

the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from

the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date

of this final action and the advisory action is not mailed until after the end of the THREE-MONTH

shortened statutory period, then the shortened statutory period will expire on the date the advisory action

is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

the advisory action. In no event, however, will the statutory period for reply expire later than SIX

MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Scott R. Wilson whose telephone number is 571-272-1925. The examiner can normally be

reached on M-F 8:30 - 4:30 Eastern.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Nathan Flynn can be reached on 571-272-1915. The fax phone number for the organization where this

application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through

Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC)

at 866-217-9197 (toll-free).

NATHAN JOELANN SUPERVISORY PATENT EXAMINE

srw

April 15, 2005